

















Nanolaminate encapsulation									
Producer	Encansulation	Number of lavers	WVTP	Crack Onset					
rioducci	Structure	Humber of layers	(g.m ⁻² .day)	Strain (%)					
<i>Vitex (</i> Barix)	[acrylate/Al ₂ O ₃] _n	10	~ 1 × 10⁻ ⁶	0.8					
Philips (NONON)	[SiN _x /SiO _x] _n	'12' + topcoat	3.6 × 10 ⁻⁶	1.0					
GE (graded UHB)	[SiN _x /SiO _x] _n	'5'	8.6 × 10 ⁻⁶	-					
Applied Materials	(SiN/lacquer) ₂	4	~ 1 × 10 ⁻⁵	1.0					
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	Low Stress UV Curable Hyperbranched Polymer Nanocomposites						
	Microbattery, layer thickness 500 μm		Polyether HBP		SU8		
	6		2017 20. 11.21.21.21.21.21.21.21.21.21.21.21.21.2				
	20KV X25 1	nm 0000 PC-SEM		())	(0		
	Resist	Layer thickness, L (μm)	Aspect ratio, AR	Residual stress (MPa)	Fabrication time (h)	FOM	
	Resist Polyether HBP	Layer thickness, L (μm) 850	Aspect ratio, AR	Residual stress (MPa) 2.4	Fabrication time (h) 0.5	FOM 5454	
	Resist Polyether HBP Polyester HBP	Layer thickness, L (μm) 850 500	Aspect ratio, AR 7.7 3.3	Residual stress (MPa) 2.4 4.5	Fabrication time (h) 0.5 0.5	FOM 5454 733	
	Resist Polyether HBP Polyester HBP SU-8	Layer thickness, L (μm) 850 500 250	Aspect ratio, AR 7.7 3.3 11	Residual stress (MPa) 2.4 4.5 25	Fabrication time (h)0.50.53	FOM 5454 733 37	
Jin \ Schi	Resist Polyether HBP Polyester HBP SU-8 YH., J. Micromech. Microeng	Layer thickness, L (μm) 850 500 250 2, 17, 1147-1153 (2007). roeng. 18, 045022 (2008).	Aspect ratio, AR 7.7 3.3 11	Residual stress (MPa) 2.4 4.5 25	Fabrication time (h)0.50.53	FOM 5454 733 37	



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